
Benzoyl peroxide: a cause of skin injury in Japan?

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To the editor: A recently published article has reported a case of periorbital skin injury in a healthy 19-year-old man after the short-term use (90 min) of a transparent medical dressing (Tegaderm; 3M Health Care, St. Paul, MN, USA) [1]. In this case report, the authors speculated that the regular use of a topical acne treatment wash that contained 5% benzoyl peroxide was a plausible cause of this injury [1]. A strong oxidant benzoyl peroxide, that is approved by the United States Food and Drug Administration, is currently used to prevent or treat acne in the United States. However, it should be emphasized that repeated or prolonged contact with this compound may cause skin sensitization [2]. In relation to this issue, we have reviewed the contents of available ointments and washes used

for the treatment of acne in Japan, in cooperation with Nichiban Corporation (Tokyo, Japan). Also, we have found that none of these products containing benzoyl peroxide manufactured in Japan. We note that benzoyl peroxide is currently not approved by the Japanese government for medical use. However, it is still important to keep in mind, regarding this issue, that it is possible for people in Japan to personally import ointments or washes for acne that contain benzoyl peroxide [3].

References

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